

 <b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)	ATTY DOCKET NO. ITL.1026US (P16713)	SERIAL NO. 10/688,521
	APPLICANT(S): ROBERT P. MEAGLEY ET AL.	
	FILING DATE: October 17, 2003	GROUP ART UNIT: 1752

### U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A.						
	B.						
	C.						
	D.						
	E.						
	F.						
	G.						
	H.						
	I.						

### FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	J.							
	K.							
	L.							
	M.							
	N.							
	O.							
	P.							

### OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

ACN	Q.	Robert P. Meagley and Michael D. Goodner, U.S. Patent Application Serial No. 10/679,793, filed 10/06/2003, entitled "Increasing the Etch Resistance of Photoresists"
	R.	
	S.	
	T.	
	U.	
	V.	
	W.	

EXAMINER <i>Shirley C. Walker</i>	DATE CONSIDERED <i>March 9, 2005</i>
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\*EXAMINER: Initial reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.